

## **AMENDMENTS TO THE CLAIMS**

This listing of claims replaces all previous versions and listings of claims in this application.

### **Claim Listing:**

Claims 1-2: (Canceled).

3. (Previously Presented) An apparatus for removing a resist film used in a lithographic process, said apparatus comprising:

means for spraying saturated steam onto said resist film,

wherein said resist film is peeled off by an action of said saturated steam.

4. (Previously Presented) An apparatus as set forth in claim 3, wherein the temperature of said saturated steam at the target surface is within the range of 70° to 100°C.

Claims 5-22: (Canceled).

23. (Previously Presented) The apparatus of claim 3, further comprising at least one of:

means for making water act on said resist film;

means for making vapor of isopropyl alcohol act on said resist film;

means for making compressed carbonic acid gas act on said resist film;

means for adding a chemical ingredient into said steam and/or said water;

means for irradiating said resist film with ultraviolet rays;

means for applying high-frequency supersonic waves to said resist film; and

means for cooling a substrate on which said resist film is formed,

wherein said resist film is peeled off by properly combining at least one of time and/or spatial conditions, conditions on temperature, and physical and/or chemical conditions for operating each of said means.

Claims 24-34: (Canceled).